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**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant: SHIH et al.  
 Application No.: 10/666,331  
 Filed: 9/17/2003


Examiner: KORNAKOV, Michail  
 Group No.: 1746  
 Confirmation No.: 8374

Title: METHODS FOR CLEANING A SET OF  
 STRUCTURES COMPRISING YTTRIUM OXIDE IN  
 A PLASMA PROCESSING SYSTEM

**INFORMATION DISCLOSURE STATEMENT**

**OTHER DOCUMENTS**

Examiner Initials	Cite No.	Description	T
MK	1	GEORGE, H. Bola, "In-Situ Analysis of High Density Plasma Enhanced Chemical Vapor Deposition of Thin Films," October 13, 1999, 17 slides total	
MK	2	"Acetone," <a href="http://www.wikipedia.org/wiki/Acetone">http://www.wikipedia.org/wiki/Acetone</a> , 2 pages total	
MK	3	JOHNSON et al., "Reducing PFC gas emissions from CVD chamber cleaning," Solid State Technology, December 2000, 6 pages total	
MK	4	"Hydrogen Peroxide (H <sub>2</sub> O <sub>2</sub> ): the Amazing Secrets That THEY Don't Want You to Know!," <a href="http://www.h2o2-4u.com/">http://www.h2o2-4u.com/</a> , 6 pages total	
MK	5	HORIUCHI et al., "In-Situ Chamber Wall Cleaning in Processing Plasmas," 4 pages total	
	6	<del>FRIZ et al., "Coating Materials," pp. 105-130</del>	
	7	<del>YEOH et al., "Photoresist Strip on Orion2.2™ in Via First Dual Damascene Cu Structures," Trikon Technologies, 3 pages total</del>	
	8	<del>"Yttrium Oxide Products: Ideal for Titanium Processing," ZYP Coatings Inc., 8 pages total</del>	
MK	9	NELSON et al., "Yttrium Oxide Nanoparticles Prepared by Alkalide Reduction," Chem. Mater. 2002, 14, pp. 915-917	
MK	10	"Chemical of the Week: Ammonia, NH <sub>3</sub> ," <a href="http://scifun.chem.wisc.edu/chemweek/ammonia/ammonia.html">http://scifun.chem.wisc.edu/chemweek/ammonia/ammonia.html</a> , 3 pages total	
	11	<del>"Introduction," EE 4283/6283 SiC RIE lab project, MS State University, 6 pages total</del>	
MK	12	"Thermal Spray Coatings: Nature of Thermal Spray Coatings," 10 pages total, <a href="http://www.gordonengland.co.uk/tsc.htm">http://www.gordonengland.co.uk/tsc.htm</a>	
MK	13	NICKERSON et al., "Plasma Cleaning of Medical Devices," Critical Cleaning in Precision Manufacturing, 4 pages total	
MK	14	SOBOLEWSKI et al., "Electrical Optimization of Plasma-enhanced Chemical Vapor Deposition Chamber Cleaning Plasmas," J. Vac. Sci. Technol. B 16(1), Jan/Feb 1998, pp. 173 - 182	
MK	15	"Plasma Spray Process," <a href="http://www.gordonengland.co.uk/ps.htm">http://www.gordonengland.co.uk/ps.htm</a> , 3 pages total	

Examiner Signature		Date Considered	03/03/07
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<b>Form 1449 (Modified)</b>  <b>Information Disclosure Statement By Applicant</b>  (Use Several Sheets if Necessary)	Atty Docket No.	Application No.:
	LMRX-P023/P1130	10/666,331
	Applicant:	
	SHIH et al.	
Filing Date	Group	
9/17/2003	1746	

## U.S. Patent Documents &amp; Published Applications

Examiner Initial	No.	Patent or Pub App No.	Date	Patentec	Class	Sub-class	Filing Date
<i>MR</i>	1	6,679,996	01/20/2004	Yao			10/05/2000
	2	03/127049	07/10/2003	Han et al.			01/08/2002
	3	03/120099	06/26/2003	Laine et al.			10/29/2001

## Foreign Patent or Published Foreign Patent Application

Examiner Initial	No.	Document No.	Publication Date	Country or Patent Office	Class	Sub-class	Translation	
							Yes	No

## Other Documents

Examiner Initial	No.	Author, Title, Date, Place (c.g. Journal) of Publication
	4	PCT International Search Report mailed 19 MAY 2005, PCT/US04/30430
	5	Written Opinion of ISR, PCT/US04/30430
Examiner	Date Considered	
<i>u/p</i>	03/03/07	

Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

